
Dielectrics for Nanosystems 8: Materials Science, Processing, Reliability, and Manufacturing

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Table of Contents

Preface *iii*

Chapter 1
Ferroelectric Materials and Devices

Double Swing Quiescent-Current: An Experimental Detection Method of
Ferroelectricity in Very Leaky Dielectric Films *3*
S. Dueñas, H. Castán, Ó. G. Ossorio, G. Vinuesa, H. García, K. Kukli, M. Leskelä

Chapter 2
Memory Devices

(Invited) Reliability and Scaling Perspectives of HfO₂-Based OxRAM *9*
C. Cagli, J. Sandrini, G. Sassine, D. Robayo, I. Hammad, G. Molas, F. Gaillard

(Invited) Current and Voltage Control of Intermediate States in Bipolar Rram
Devices for Neuristor Applications *17*
H. García, Ó. G. Ossorio Jr., S. Dueñas, H. Castán

Chapter 3
Transistor Systems

<i>(Invited)</i> Gate-All-Around Nanosheet Field-Effect Transistors for Advanced Logic and Memory Applications: Integration and Device Features	23
<i>A. Veloso, P. Matagne, G. Eneman, H. Mertens, A. Chasin, E. Simoen, N. Horiguchi</i>	

<i>(Invited)</i> Development of CMOS-MEMS Cointegrated Pressure Sensor Using Minimal Fab Process	35
<i>Y. Liu, I. Akita, T. Matsukawa, H. Tanaka, K. Koga, K. Nemoto, S. Khumpuang, M. Nagao, Y. Morita, S. Hara</i>	

Chapter 4 High-k and Emerging Dielectrics

Whether Ge-Rich ZrO ₂ and Ge-Rich HfO ₂ Materials Have Similar Reaction on Annealing Treatment?	49
<i>L. Khomenkova, D. Lehninger, E. Agocs, P. Petrik, X. Portier, N. Korsunska, O. Melnichuk, F. Gourbilleau, J. Heitmann</i>	

<i>(Invited)</i> Development of New High-Dielectric Constant Thin Films By Combinatorial Synthesis	61
<i>T. Nagata</i>	

<i>(Invited)</i> Band Line-up of High-k Oxides on GaN	67
<i>I. Z. Mitrovic, P. Das, L. Jones, J. Gibbon, V. R. Dhanak, R. Mahapatra, T. Partida Manzanera, J. W. Roberts, R. J. Potter, P. R. Chalker, S. J. Cho, I. G. Thayne</i>	

Study of Si(100)-SiO ₂ Interface Trap Time Constant Distributions in Large Area Conventional MOSFETs-Comparison with Submicron Devices	83
<i>D. Bauza, N. Guenifi</i>	

Chapter 5 Nanomaterials and Devices

The Effect of Carbon Coatings on the Electrochemical Performance of Composite Electrodes	93
<i>G. Gonzalez, R. Gonzalez, L. Zuniga, M. Chipara, M. Alcoutlabi</i>	
Investigation of Indium Oxide Nanowire Transform to Indium Zinc Oxide (IZO) Via Solid State Reactions	105
<i>J. H. Chang, H. Y. Lo, Y. T. Tseng, C. Y. Huang, Y. S. Ding, W. W. Wu</i>	
Mid-Wavelength Infrared Responsivity of Colloidal Quantum Dot/Organic Hybrid Photodetectors	109
<i>S. B. Haftz, M. M. Al Mahfuz, D. K. Ko</i>	

Chapter 6 **Dielectric Characterization**

(Invited) Second Harmonic Generation: A Powerful Non-Destructive Characterization Technique for Dielectric-on-Semiconductor Interfaces	119
<i>I. Ionica, D. Damianos, A. Kaminski, D. Blanc-Pâlisier, G. Ghibaudo, S. Cristoloveanu, L. Bastard, A. Bouchard, X. Mescot, M. Gri, M. Lei, B. Larzelere, G. Vitrant</i>	

Chapter 7 **Surface Characterization**

(Invited) Impact of Surface Roughness of the Electrodes on the Resistive Switching in ReRam Devices	133
<i>M. Al-Mamun, A. Chakraborty, Y. Li, M. K. Orlowski</i>	

Dynamic Observation of Electromigration in High Density Electroplated Nanotwinned Copper through <i>In-Situ</i> TEM <i>F. C. Shen, C. Y. Huang, W. W. Wu</i>	145
X-Ray Photoelectron Spectroscopy Estimation of Cobalt Seed Layer Reactivity Toward Air Exposure: A Challenge? <i>A. Etcheberry, A. Lakhdari, L. Caillard, D. Suhr, M. Thiam, F. Raynal, N. Simon, A. M. Goncalves, V. Mevellec, M. Fragnaux</i>	149
Author Index	157